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Case Docket No. 3521.125 (ALJ)

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Transmitted herewith for filing is the patent application of

Inventor: **ANDREW M. HAWRYLUK, et al.**

For **METHODS FOR ANNEALING A SUBSTRATE AND ARTICLE PRODUCED BY SUCH METHODS**

Enclosed are:

1. A duplicate copy of this Transmittal Letter
2. 14 sheets of description, 10 sheets of claims, 1 sheet(s) of abstract: total of 25 sheets of specification
3. 4 sheets of informal drawing (Figures 1a-4).
4. A signed Declaration and Power of Attorney
5. A signed Small Entity Declaration
6. A check in the amount of \$909.00
7. Postcard

FILING FEE CALCULATION - CLAIMS AS FILED					(5) BASIC FEE	
(1) FOR		(2) NUMBER FILED	(3) NUMBER EXTRA	(4) RATE	SMALL	OTHER
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TOTAL CLAIMS	SMALL ENTITY	74- 20 =	54	\$9	\$486.00	
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INDEP. CLAIMS	SMALL ENTITY	5- 3 =	2	\$39	\$78.00	
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**VERIFIED STATEMENT (DECLARATION) CLAIMING SMALL ENTITY
STATUS (37 CFR 1.9(f) AND 1.27 (b)) - INDEPENDENT INVENTOR**

Docket No.
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Issue Date

Applicant/ **ANDREW M. HAWRYLUK, ET AL.**
Patentee:

Invention: **METHODS FOR ANNEALING A SUBSTRATE AND ARTICLE PRODUCED BY SUCH METHODS**

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METHODS FOR ANNEALING A SUBSTRATE AND ARTICLE PRODUCED BY SUCH METHODS

Background of the Invention

5 1. Field of the Invention

This invention is directed to methods for annealing a substrate using a pulse of particles such as electrons, protons, ions, or other, neutral particles. The invention is also directed to integrated devices or circuits made by such methods. The substrate can be composed of silicon, gallium arsenide, or other semiconductor species, or can
10 include an insulative material with a relatively thin-film of semiconductor material formed thereon. The apparatus and methods can be used to anneal or activate integrated devices or circuits formed in the substrate, and to form low-resistance silicide regions thereon. Such integrated devices can include active devices such as transistors or diodes, or passive devices such as resistors or capacitors. For example,
15 the apparatus and method can be used to anneal a substrate to obtain a relatively high crystalline state therein, or to activate the substrate to incorporate dopant atoms into the substrate's crystalline lattice, to achieve proper electrical performance of the integrated devices.

20 2. Description of the Related Art

In forming integrated devices in a semiconductor substrate it is common to use ion implantation to introduce dopant atoms of appropriate species into the substrate to form n-type or p-type regions. Immediately after implantation the dopant atoms are not generally positioned within the substrate where they can be useful to achieve
25 proper electrical performance of the integrated device being formed. Also, the dopant atoms are accelerated to relatively high-energies by ion implanters. Therefore, upon colliding with the substrate the dopant atoms cause considerable damage to the

substrate by breaking chemical bonds therein. The crystalline structure of the substrate must be restored, and the dopant atoms incorporated into it, in order to obtain proper electrical performance of the integrated devices. Annealing is typically performed by heating the substrate so that the dopant atoms and substrate atoms
5 have sufficient energy to realign. Of considerable importance in the manufacture of integrated devices or circuits is the "throughput" that a manufacturer can obtain with a process for forming integrated devices, and the cost necessary to achieve that throughput. It is always desirable to reduce the number of steps in a process for forming an integrated device or circuit as long as the integrated circuits or devices
10 suffer no significant degradation in performance as a result thereof. Of course, a process that not only reduces the number of steps required to form an integrated device or circuit, but also increases its electrical performance, would be highly desirable.

In the annealing process it is desirable that the heating of the doped regions
15 be uniform so that all regions are annealed similarly and so perform similarly. An annealing process should therefore have the capability to uniformly anneal doped regions of a substrate.

Another problem related to annealing is the necessity to limit the diffusion of dopant atoms within the circuit. With the ongoing reduction of device dimensions
20 over time to achieve faster switching speeds and to incorporate more devices per unit area within the substrate, it becomes increasingly important to restrict diffusion. Otherwise, the dopant atoms can create leakage paths between source, drain and/or gate regions, which either impair or destroy electrical performance of the integrated device. It would be desirable to provide a method that reduces or eliminates diffusion
25 of the dopant atoms in a substrate.

Summary of the Invention

The invented apparatus overcomes the above-stated disadvantages. A first method of this invention includes annealing at least one region of a substrate with

charged particles. The charged particles can be electrons, protons, ions, alpha particles, or neutral particles. The substrate can be composed of a semiconductor material, for example. The particles can be p-type dopant atoms including boron (B), aluminum (Al), gallium (Ga), indium (In), and palladium (Pd), or n-type dopant atoms species including arsenic (As), phosphorus (P), antimony (Sb), titanium (Ti), platinum (Pt), gold (Au), and oxygen (O). The particles can be used to anneal dopant or other atoms previously implanted into the substrate. Alternatively, the species and energies of the particles can be selected so as to simultaneously implant and anneal the substrate. This alternative implementation of the method requires the particles be a dopant species because implantation and activation are performed in a single step. If no change in the electrical state of the substrate is required, the particles can include atoms with the same valency as the substrate. Such ions include one or more of carbon (C), silicon (Si), and germanium (Ge) or other species with the same valency as the substrate.

The particles can be applied to the substrate with a predetermined flux, energy, pulse duration, and dosage. The energy of the particles can be determined based upon one or more of the following criteria:

(1) the particles have an energy corresponding to an absorption length that is equal to or greater than the desired junction depth;

(2) the particle species is chosen to correspond to the desired dopant and the dose corresponds to the desired doping concentration; and

(3) the particles have an energy, flux, and pulse duration to raise the temperature of the irradiated region sufficiently high for annealing or activation to occur.

The energy of the charged particles can range from one-tenth (0.1) to one-hundred (100) kilo-electron-Volts, the range for electrons being from five (5) to seven (7) keV. The charged particle flux generally ranges from 10^{12} to 10^{18} particles per square centimeter at the surface of the substrate. The particle flux incident on the surface of the substrate can be from 5×10^{12} to 5×10^{13} particles per square

centimeter. The pulse duration of the particles can be from 10^{-9} to 10^{-4} seconds. However, within the limitations of presently available equipment, the pulse duration of the particles can be in a range from about 5×10^{-7} to 10^{-4} seconds. The energy dose can be from one-tenth (0.1) to one (1.0) Joules/cm².

- 5 The substrate can include dopants with a predetermined distribution in the substrate and the pulse duration of the particle annealing beam can be limited to prevent significant change in the dopant distribution due to diffusion. The doped region can be amorphous and the underlying substrate can be crystalline. The particle beam can produce a uniform temperature distribution in the amorphous
- 10 region sufficient to promote crystallization of the amorphous region with the crystalline portion of the substrate acting as a seed crystal. A second method of the invention includes generating particles, accelerating the particles toward a substrate, and focusing the particles to increase the flux of the particles so that they have sufficient flux and energy to anneal a region of the substrate. The particles can
- 15 include electrons, protons, ions, alpha particles, and other neutral atoms. As with the first method, the second method can be performed with a multicusp generator and an accelerator, and optional focusing lens and beam neutralizer. Most of these elements are contained in a conventional ion implanter. If the particles are dopant species, the energies, the flux and the pulse duration of the particle beam can be selected or
- 20 arranged to provide the desired dopant concentration and distribution and, possibly, to achieve activation concurrently with irradiation.

It is an object of the invention to provide an apparatus and methods that can be used to produce an even temperature distribution within a doped region undergoing treatment.

- 25 It is an object of the invention to provide an apparatus and methods that can be used to anneal a substrate without significantly changing the dopant distribution therein.

These together with other features and advantages, which will become subsequently apparent, reside in the details of the invented apparatus and method as

more fully hereinafter described and claimed, reference being made to the accompanying drawings, forming a part hereof, wherein like numerals refer to like parts throughout the several views.

5 **Brief Description of the Drawings**

Figs. 1A-1C are cross-sectional views of a first method of the invention to anneal a region of a substrate with charged particles;

Figs. 2A-2C are cross-sectional views of a second method of the invention to implant and anneal a region of a substrate with charged particles;

10 Fig. 3 is a cross-sectional view of an apparatus used to generate, accelerate, and focus charged particles on a substrate; and

Fig. 4 is a cross-sectional view of a magnetic filter of the apparatus of Fig. 3.

Description of the Preferred Embodiments

15 As used herein, the following terms have the following meanings:

"**Absorption length**" is a well-known parameter, and is defined as the thickness of a particular material required to reduce the intensity of the energy of the charged particles propagating in such material to $1/e$, or 36.8 percent, of its initial intensity.

20 "**Anneal**" includes "activation", "crystallization" or "recrystallization" within its scope, and refers to raising and subsequently lowering the temperature of a relatively disordered semiconductor region either to crystallize such region to be integral with a crystalline semiconductor substrate, to activate dopant atoms by incorporating them into the crystalline lattice of the semiconductor region, or to incorporate metal atoms
25 within a semiconductor region to form relatively low-resistance silicide contacts to coupled conductive lines to a terminal of an integrated device formed on a substrate.

"**Depth**" refers to the distance to which a region extends into the substrate in a direction perpendicular to the substrate's upper major surface as viewed in the perspective of the Figures.

"Disordered region" refers to a semiconductor region in which the atoms contained therein are not relatively ordered either because they are in a non-crystalline state due to damage or amorphization caused by implantation of dopant or non-dopant atoms, and/or because they include dopant atoms that have not been
5 incorporated into the crystalline lattice of such region by activation, for example.

"Energy" refers to the kinetic energy of the charged particles gained by an acceleration applied to an implantation machine.

"Flux" refers to the number of charged particles per unit area (usually expressed in particles per square centimeter units) incident to the top surface of the
10 region of the substrate to be annealed.

"Integrated device" can refer to an active device such as a transistor or diode (including bipolar and complementary metal-insulative semiconductor field-effect transistor (MISFET)), or can refer to a passive device such as a resistor or capacitor. A MISFET includes a complementary metal-oxide field-effect transistor
15 (MOSFET) within its definition.

"Power" as applied to charged particles, is defined as the flux of the charged particles multiplied by the energy of the charged particles, further multiplied by the pulse duration over which the charged particles are applied to the substrate.

"Process" as used herein is broadly defined and generally refers to a method
20 for forming integrated devices or circuits on a substrate.

"Thermal diffusion coefficient" is defined as $k / \rho \cdot C$ where k is the thermal conductivity (J/sec•cm•°C), ρ is the density (gm/cm³), and C is the heat capacity (J/gm•°C).

"Thickness" refers to the distance between the upper and lower surfaces of a
25 region in a direction perpendicular to such surfaces as viewed in the perspective of the Figures.

1. First Generalized Embodiment of the Invented Method

Figs. 1A - 1C are views of a method for annealing a region of a semiconductor

substrate using charged particles. The semiconductor substrate 1 can include silicon, gallium arsenide, or other semiconductor material. The substrate 1 can be in the form of a wafer, for example. The wafer can be six, eight, twelve, or sixteen inches in diameter and on the order of seven-hundred-fifty microns in thickness. Alternatively, the substrate 1 can be a layer of semiconductor material formed on an insulative layer or material. For example, the substrate 1 could be a layer of silicon in a silicon-on-insulator (SOI) or a silicon-on-sapphire (SOS) structure. The substrate 1 could also be a relatively thin-film of semiconductor material such as poly-silicon or crystalline silicon formed on an insulative substrate as is used in the manufacture of thin-film transistors for flat panel displays and the like. The major surface 3 of the substrate 1 extends in a direction perpendicular to the plane of Figs. 1A - 1C. Such major surface can be oriented in $\langle 100 \rangle$ or $\langle 111 \rangle$ directions defined by Miller indices, as is well-known to persons of ordinary skill in this technology.

In Fig. 1A, the substrate 1 is implanted with atoms 4. The atoms 4 are distributed in region 2 of the substrate to a predetermined depth corresponding to the thickness t of the region 2. The major surface 3 of the substrate 1 is the entry point of the particle beam. In general, the greater the atomic weight of such atoms and the less the implantation energy of such atoms, the shallower the depth to which the implanted atoms travel into the substrate 1 relative to its major surface 3.

Conversely, the less the atomic weight of the implanted atoms and the greater their implantation energy, the greater the thickness t to which the region 2 extends into the substrate 1.

The method step of Fig. 1A can be used to implant dopant atoms to form a source or drain region of an integrated transistor in the substrate 1, or to form the cathode or anode of a diode, for example. Such step can also be used to implant dopant atoms into the substrate 1 to form an integrated resistor, or conductive portions of an integrated capacitor, or a conductive line extending between terminals of integrated devices that are coupled together, for example. If the implanted atoms are used to dope the region 2 such atoms are either p-type or n-type. For a silicon

substrate 1, p-type dopant atoms include boron (B), aluminum (Al), gallium (Ga), indium (In), and palladium (Pd), and n-type dopant atoms species include arsenic (As), phosphorus (P), antimony (Sb), titanium (Ti), platinum (Pt), gold (Au), and oxygen (O). The composition of silicides and the species of refractory metal atoms
5 that can be used to form such silicides are described in, for example, U.S. Patent No. 5,888,888 issued March 30, 1999 to Somit Talwar et al., which is incorporated herein by reference. In addition the atoms 4 implanted into the region 2 can be electrically neutral species such as silicon (Si) or germanium (Ge) in silicon substrate 1. For example, the atoms can be implanted into the region 2 of the substrate 1 using a
10 device such as the 9500 XR Ion Implanter machine commercially-available from Applied Materials, Inc. of San Jose, California.

The implantation of the atoms of Fig. 1A into the substrate 1 damages the crystallinity of the substrate in the region 2 affected by the implanted atoms. More specifically, the implanted atoms collide with atoms of the substrate 1 and break
15 chemical bonds between some of the substrate atoms, rendering the substrate atoms relatively disordered in the region 2. The atoms in the region 2 can be so disordered as to be considered 'amorphous' and thus lacking any significant crystallinity. In addition, the implanted atoms are generally not positioned within the crystalline lattice of the substrate 1 within the region 2 immediately after they are implanted. If the
20 implanted atoms are dopant species it is especially important to anneal the region 2 to restore the crystallinity of the substrate 1 and to position at least some of the implanted atoms at sites within the lattice of the semiconductor material. Otherwise, the region 2 may not exhibit the desired electrical performance upon application of electric current/voltage thereto. Accordingly, the region 2 must be annealed to obtain
25 proper electrical performance. The manner of accomplishing this in the subject method is now described with reference to Fig. 1B.

Importantly, in Fig. 1B, the method includes a step of annealing the region 2 with particles. The particles can be electrons, protons, ions, alpha particles, or neutral atoms. The different types of atoms that can be used in this step can include virtually

any ion that does not adversely affect electrical performance. Such atoms can include dopant species such as boron (B), aluminum (Al), gallium (Ga), indium (In), and palladium (Pd), arsenic (As), phosphorus (P), antimony (Sb), titanium (Ti), platinum (Pt), gold (Au), and oxygen (O). The atom species can also be one that is electrically neutral such as silicon (Si), or germanium (Ge). These atomic species have the same valence as common substrate materials such as silicon and thus have no significant impact upon the electrical characteristics of the region 2. Other atomic species include the noble gases such as helium (He), neon (N), argon (Ar), xenon (Xe), or krypton (Kr), for example. Hydrogen (H) and nitrogen (N) are also candidates. These gaseous species provide the advantage of being relatively easy to ionize. Fluorine (F) and chlorine (Cl) could also be used but are generally less preferred because of their toxic and highly reactive natures. Sodium (Na) and potassium (K) are generally shunned for use in semiconductor materials because they adversely affect electrical performance of integrated devices. Because the flux of the charged particles necessary to anneal the region 2 is relatively small (approximately 10^{13} to 10^{18} particles per square centimeter) almost any atomic species can be used to anneal the region 2 of the substrate 1.

The energy, flux, and pulse duration of the particle beam 6 that is required to anneal the region 2 generally depends upon the thickness t of the region 2 and the type of material composing such region 2. In general the greater the energy of the particles, the greater the thickness t to which the particles can anneal the region 2. Conversely, the less the energy of the particles the less the thickness t to which the region 2 extends.

Exemplary ranges for the energy, flux, and pulse duration of the particles 6 applied to anneal the region 2 are as follows. The energy of the charged particles 4 can range from one-tenth (0.1) to one-hundred (100) kilo-electronVolts, the most preferred range being from five (5) to seven (7) keV for electrons. The charged particle dose generally ranges from 10^{12} to 10^{18} particles per square centimeter at the surface 3 of the substrate 1. Determination of the pulse duration of the particle

irradiation 4 to be applied to the region 2 should utilize the following considerations.

In general, it is desirable to heat the region 2 uniformly from surface 3 to lower surface 5 of the dopant profile. The pulse duration should also be sufficiently limited so that minimal dopant diffusion occurs and so that the thermal diffusion length is

5 limited to the desired annealing depth or by practical limitations of the equipment.

This minimizes the power required to anneal the region. In general, the pulse duration can be from 10^{-9} to 10^{-4} seconds. However, commercially-available implantation equipment limits the pulse duration to a range from about 5×10^{-7} to 10^{-4} seconds. With implantation equipment currently available greater implant voltages

10 and longer pulse times than the most preferred pulse duration are required.

Nonetheless, effective annealing can be performed with the limitations of commercially-available equipment.

For example, if the thickness t is one-hundred (100) nanometers and electrons are used for the particles 6, a six (6) kiloelectronVolt (keV) electron beam that is

15 pulsed for one (1) microsecond can be used which penetrates four-tenths (0.4) microns into the substrate 1. Such penetration depth is four times the thickness t of the region 2. In this case thermal diffusion resulting from the electrons heats the substrate to nine-and-one-half (9.5) microns, which is much thicker than the thickness t . Nonetheless, the pulse duration is sufficiently short to anneal the region 2 without

20 degradation in the dopant profile.

As another example protons can be used as the particles 6 with an energy of 6 keV. If the thickness t of the region 2 is one-hundred (100) nanometers the proton range into the substrate 1 is about the same as the thickness t of the region 2. The thermal diffusion length for the protons in this example is 9.5 microns for a pulse

25 duration of one (1) microsecond, almost one hundred times as great as the thickness of the region 2 in this example. However the pulse duration is sufficiently short to prevent dopant diffusion beyond the region 2.

Particles larger than protons would be even less penetrating into the substrate but limitations of commercially-available equipment would limit the pulse duration to

the microsecond region.

The following tables illustrate range versus kinetic energy for various charged particles in a silicon substrate:

5

Table 1. Range of Protons in Silicon

Kinetic Energy (keV)	Range (microns)
6	0.08
12	0.15
18	0.20

10

Table 2. Range of Electrons in Silicon

Kinetic Energy (keV)	Range (microns)
6	0.4
12	1.1
18	2.2

15

Table 3. Range of Alpha Particles in Silicon

Kinetic Energy (keV)	Range (microns)
6	0.063
12	0.12
18	0.18

20

25

Determining kinetic energies corresponding to other ranges than those stated above can be performed by interpolation or extrapolation of the kinetic energies and ranges. In addition such information is available from numerous sources including National

Institutes of Standards (NIST) and others.

The exposure of the region 2 to the particle beam 6 heats the region to near its melting point so that the atoms therein can rearrange themselves into a relatively ordered state as compared to that resulting from performance of the implanting step in Fig. 1A. Therefore if the region 2 contains dopant atoms such atoms rearrange themselves with the substrate atoms so that the dopant atoms are electrically active.

If the region 2 is composed of amorphous atoms of the substrate material and the substrate 1 is crystalline, the power imparted by the particle beam 6 can be sufficient to trigger the recrystallization of the region 2 to the surface 5. Depending on the temperature distribution in the amorphous region the substrate 1 can act as a seed upon which the region 2 crystallizes so that is crystallographically integral with the substrate 1. In Fig. 1C, the region 2 is illustrated with 'x' hatching to indicate that such region is relatively ordered after annealing with the charged particles 6.

Figs. 2A - 2C are a second embodiment of the invented method. In Fig. 2A, the substrate 1 is shown in its initial state before performance of the second embodiment of the method. In Fig. 2B, particles 6 are implanted into the substrate 1 to form the region 2. The particles 6 can be a dopant. The energy, flux, and pulse duration of the particle beam 6 is sufficient to implant these particles into the region 2, and also to anneal the region. Accordingly the region 2 can be doped and activated in one step, a significant advantage over previous methods. In Fig. 2C, the region 2 crystallizes after being triggered by the charged particle beam 6 so that the region 2 crystallizes with in a relatively ordered form represented by the 'x' hatching in Fig. 2C.

An option for the generation of electrons, protons, or other ions is a multicusp plasma generator 106 shown in Fig. 3. The multicusp generator 106 includes an element 108 that can be a direct current (DC) or radio-frequency (RF) element. The element 108 is coupled to a DC or RF source via conductors 110. The water-cooled jacket 112 surrounds the element 108 and circulates a flow of coolant such as water to cool portions of the generator 106 relatively near the element 108. The conduit

114 is coupled to a pressurized gas source to receive an atomic species from which plasma is to be generated by the element 108 within enclosure 116. Such gas source can include hydrogen, helium, neon, nitrogen, oxygen, argon, xenon, or krypton, for example. The generator 106 also includes a magnetic filter 118 that generates a
5 relatively uniform density of the charged particles 6, at a central area thereof. The apparatus 106 further includes extractor electrodes 120, 122 to extract charged particles from the enclosure 116. The electrode 120 is coupled to an electrically positive voltage source to accelerate electrons or negative ions generated within the enclosure 116 via the element 108. The electrode 122 is coupled to an electrically
10 negative voltage source to accelerate protons or positive ions generated by the element 108. The apparatus 106 can include an accelerator unit 124 that includes spaced electrodes that apply either positive or negative voltage appropriate for the charged particles to accelerate such particles. The accelerator unit 124 also focuses the charged particles so that their flux is increased several fold (for example, twenty)
15 upon exiting the enclosure 116. The focused, charged particle beam 6, may, after acceleration, be neutralized by the addition of opposite charge before striking the substrate 10 on x-y stage 126 with sufficient energy to anneal regions thereof.

In Fig. 4, a cross-section of the magnetic filter 118 is shown. The magnetic filter 118 includes permanent magnets 128 arranged at constant radial intervals in a
20 circular arrangement in which the poles of adjacent magnets are reversed relative to one another. The permanent magnets 128 generate magnetic-field cusps that render the density of the charged particles in the central portion 130 relatively uniform. The energy distribution of the charged particles at the substrate 10 can be rendered relatively uniform using the magnetic filter 118.

25 In operation a gas flow from which plasma is to be generated is introduced into the enclosure 116. The element 108 is activated by application of DC or RF voltage/current thereto via conductors 110 to excite the gas present in the enclosure 116 to generate plasma. Either a positive voltage is applied to the electrode 120 or a negative voltage is applied to the electrode 122, depending upon whether the

charged particles desired to be used have positive or negative charges. Voltage is also applied to the elements of the accelerator unit 124 to accelerate and focus the charged particles at the substrate 10. The charged particles collide with and anneal one or more regions of the substrate 10.

5 The many features and advantages of the present invention are apparent from the detailed specification and thus, it is intended by the appended claims to cover all such features and advantages of the described methods and article produced thereby which follow in the true spirit and scope of the invention. Further, since numerous modifications and changes will readily occur to those of ordinary skill in the art, it is
10 not desired to limit the invention to the exact construction and operation illustrated and described. Accordingly, all suitable modifications and equivalents may be resorted to as falling within the spirit and scope of the claimed invention.

What is claimed is:

1. A method comprising the step of annealing at least one region of a semiconductor substrate with a pulsed beam of particles having a time duration less than or equal to 10^{-4} seconds.

5

2. A method as claimed in claim 1 wherein the substrate includes an amorphous region positioned in contact with the substrate and the particle beam heats the amorphous region sufficiently to convert the amorphous region into a crystalline region with a crystal orientation aligned to the crystal orientation of the
10 substrate due to the substrate acting as a seed for the crystalline region.

3. A method as claimed in claim 1 wherein the particles in the beam include electrons.

15 4. A method as claimed in claim 1 wherein the particles in the beam include protons.

5. A method as claimed in claim 1 wherein the particles in the beam include ions.

20

6. A method as claimed in claim 1 wherein the particles in the beam include ionized gas molecules.

7. A method as claimed in claim 1 wherein the particles in the beam
25 include neutral atoms.

8. A method as claimed in claim 1 wherein the particles in the beam include molecules containing a dopant atomic species.

9. A method as claimed in claim 1 wherein the particles contain a predetermined dopant atomic species, the energy of the particles is sufficient to implant the dopant atomic species to a predetermined depth, the dose of particles is sufficient to produce a predetermined dopant concentration in the substrate, and the pulse duration of the beam of particles is sufficiently short to anneal the implanted region of the substrate.

10. A method as claimed in claim 1 wherein the particles contain a predetermined dopant species implanted with a predetermined energy that produces a doped region in the substrate extending to a doping depth, and thermal energy imparted by the particles has a diffusion length over the duration of the particle beam pulse that is less than 100 microns.

11. A method as claimed in claim 1 wherein the particles include at least one atom of boron (B), aluminum (Al), gallium (Ga), indium (In), arsenic (As), phosphorus (P), or antimony (Sb).

12. A method as claimed in claim 1 wherein the particles have the same valency as the substrate.

13. A method as claimed in claim 12 wherein the substrate is composed of silicon, and the particles include at least one atom of silicon (Si) or germanium (Ge).

14. A method as claimed in claim 1 wherein the particles are produced from a gas including at least one of hydrogen (H), helium (He), neon (Ne), nitrogen (N), oxygen (O), argon (Ar), xenon (Xe), and krypton (Kr).

15. A method as claimed in claim 1 wherein the particles include alpha particles.

16. A method as claimed in claim 1 wherein the energy of the particles is in a range from one-tenth (0.1) to one-hundred (100) kilo-electron-Volts.

17. A method as claimed in claim 1 wherein the energy of the particles is in
5 a range from five (5) to seven (7) kilo-electron-Volts.

18. A method as claimed in claim 1 wherein the particle dose ranges from 10^{12} to 10^{18} particles per square centimeter at the surface of the substrate.

10 19. A method as claimed in claim 1 wherein the dose of particles ranges from 5×10^{12} to 5×10^{13} particles per square centimeter at the substrate.

20. A method as claimed in claim 1 wherein the energy dose of a single pulse of the particles is from one-tenth (0.1) to one (1.0) Joules/cm².

15

21. A method as claimed in claim 1 wherein the substrate includes at least one relatively disordered region in contact with a relatively ordered region of the substrate, and the energy of the particles is sufficient to heat the disordered region through to the ordered region so that the disordered region recrystallizes with the
20 same crystallographic orientation as the relatively ordered region of the substrate.

22. A method as claimed in claim 1 wherein the substrate includes a semiconductor material.

25 23. A method as claimed in claim 1 wherein the substrate includes silicon.

24. A method as claimed in claim 1 wherein the substrate includes a relatively thin layer of semiconductor material on an insulative material.

25. A method as claimed in claim 1 wherein the substrate includes dopant atoms and the particle beam heats and melts the substrate so that the dopant atoms are incorporated into the substrate on recrystallization.

5 26. At least one integrated transistor device formed on a semiconductor substrate and having source and drain regions annealed by a pulsed particle beam having a time duration of 10^{-4} seconds or less.

10 27. A method comprising the steps of:
a) generating a pulse of charged particles having a time duration between 10^{-7} and 10^{-4} seconds;
b) accelerating the charged particles toward a substrate; and
c) concentrating the charged particles to increase the flux of the particles to produce a dose sufficient to anneal a region of the substrate
15 in the duration of the pulse.

28. A method as claimed in claim 27 wherein steps (a) - (c) are performed with a multicusp generator.

20 29. A method as claimed in claim 27 wherein the charged particles include electrons.

30. A method as claimed in claim 27 wherein the charged particles include protons.

25 31. A method as claimed in claim 27 wherein the charged particles include ions, the method further comprising the step of:
d) ionizing a gas to produce the ions.

32. A method as claimed in claim 31 wherein the ions include a predetermined dopant atomic species contained in the ionized gas.

33. A method as claimed in claim 32 wherein energies of the ions are
5 sufficient to dope the implanted region of the substrate to a predetermined depth.

34. A method as claimed in claim 32 wherein the dose of implanted ions is sufficient to produce a predetermined dopant concentration in the substrate.

10 35. A method as claimed in claim 31 wherein the dose, energy, and pulse duration of the particles is sufficient to anneal the doped region of the substrate.

36. A method as claimed in claim 31 wherein the ions include at least one atom of boron (B), aluminum (Al), gallium (Ga), indium (In), arsenic (As), phosphorus
15 (P), or antimony (Sb).

37. A method as claimed in claim 31 wherein the ions include at least one of silicon (Si) and germanium (Ge).

20 38. A method as claimed in claim 31 wherein the ions are produced from a gas including at least one of hydrogen (H), helium (He), neon (Ne), nitrogen (N), oxygen (O), argon (Ar), xenon (Xe), and krypton (Kr).

39. A method as claimed in claim 27 wherein the charged particles include
25 alpha particles.

40. A method as claimed in claim 27 wherein the energy of the charged particles is in a range from one-tenth (0.1) to one-hundred (100) kilo-electron-Volts.

41. A method as claimed in claim 27 wherein the energy of the charged particles is in a range from five (5) to seven (7) kilo-electron-Volts.

42. A method as claimed in claim 27 wherein the particle dose ranges from
5 10^{12} to 10^{18} particles per square centimeter at the surface of the substrate.

43. A method as claimed in claim 27 wherein the dose of particles ranges from 5×10^{12} to 5×10^{13} particles per square centimeter.

10 44. A method as claimed in claim 27 wherein the particles are applied to the substrate in a pulse, and the pulse duration of the particles is from 10^{-9} to 10^{-4} seconds.

45. A method as claimed in claim 27 wherein the particles are applied to the
15 substrate in a pulse, and the pulse duration of the particles is from 5×10^{-7} to 5×10^{-6} seconds.

46. A method as claimed in claim 27 wherein the energy dose can be in a range from one-tenth (0.1) to one (1.0) Joules/cm².

20

47. A method as claimed in claim 27 wherein the substrate includes an amorphous region positioned in contact with the substrate and the charged particles heat the amorphous region sufficiently trigger recrystallization of the amorphous region through to the crystalline substrate so that the new crystalline material has the
25 same crystallographic orientation as the substrate.

48. A method as claimed in claim 27 wherein the substrate includes a semiconductor material.

49. A method as claimed in claim 27 wherein the substrate includes silicon.

50. A method as claimed in claim 27 wherein the substrate includes a relatively thin layer of semiconductor material on an insulative material.

5

51. A method as claimed in claim 27 wherein the substrate includes dopant atoms and the particle beam heats and melts the substrate so that the dopant atoms are incorporated into the substrate so as to be electrically-active upon cooling and recrystallization of the substrate.

10

52. A method comprising the step of implanting dopant atoms into a semiconductor substrate with sufficient energy so that the dopant atoms are distributed to a predetermined depth from the surface of the substrate, the energy, dose and pulse duration imparted by the dopant atoms sufficient to raise the temperature of the substrate atoms to permit annealing of the dopant atoms.

53. A method comprising the steps of annealing at least one integrated device formed in a semiconductor substrate with a pulsed beam of particles having a duration between 10^{-10} seconds and 10^{-4} seconds.

20

54. A method as claimed in claim 53 wherein the particles include electrons.

55. A method as claimed in claim 53 wherein the particles include protons.

25

56. A method as claimed in claim 53 wherein the particles include ions.

57. A method as claimed in claim 53 wherein the particles include a predetermined species of dopant atom, the energies of the particles are sufficient to implant to the predetermined depth, and the energy, dose, and pulse duration are

predetermined to anneal the implanted region of the substrate.

58. A method as claimed in claim 53 wherein the ions are implanted with an energy that produces a doped region in the substrate extending to a predetermined depth and the thermal energy imparted by the ions has a diffusion length, during the duration of the pulse, that is less than one-hundred (100) microns.

59. A method as claimed in claim 53 wherein the ions include at least one boron (B), aluminum (Al), gallium (Ga), indium (In), arsenic (As), phosphorus (P), and antimony (Sb).

60. A method as claimed in claim 53 wherein the particles include at least one atom of silicon (Si) and germanium (Ge).

61. A method as claimed in claim 53 wherein the particles are produced from a gas including at least one of hydrogen (H), helium (He), neon (Ne), nitrogen (N), oxygen (O), argon (Ar), xenon (Xe), and krypton (Kr).

62. A method as claimed in claim 53 wherein the particles include alpha particles.

63. A method as claimed in claim 53 wherein the energy of the particles is in a range from one-tenth (0.1) to one-hundred (100) kilo-electron-Volts.

64. A method as claimed in claim 53 wherein the energy of the particles is in a range from five (5) to seven (7) kilo-electron-Volts.

65. A method as claimed in claim 53 wherein the particle dose ranges from 10^{12} to 10^{18} particles per square centimeter at the surface of the substrate.

66. A method as claimed in claim 53 wherein a dose of particles ranges from 5×10^{12} to 5×10^{13} particles per square centimeter.

67. A method as claimed in claim 53 wherein the particles are applied to the substrate in a pulse, and the pulse duration of the particles is from 10^{-9} to 10^{-4} seconds.

68. A method as claimed in claim 53 wherein the particles are applied to the substrate in a pulse, and the pulse duration of the particles is from 5×10^{-7} to 5×10^{-6} seconds.

69. A method as claimed in claim 53 wherein the dosage of energy can be from one-tenth (0.1) to one (1.0) Joules/cm².

70. A method as claimed in claim 53 wherein the substrate includes at least one relatively disordered region in contact with a relatively ordered region of the substrate, and the energy of the particles, the dose and the pulse duration is sufficient to heat the disordered region through to the ordered region so that the disordered region recrystallizes with the same crystallographic orientation as the relatively ordered region of the substrate.

71. A method as claimed in claim 53 wherein the substrate includes a semiconductor material.

72. A method as claimed in claim 53 wherein the substrate includes silicon.

73. A method as claimed in claim 53 wherein the substrate includes a relatively thin layer of semiconductor material on an insulative substrate.

Abstract of the Disclosure

A method of this invention includes annealing at least one region of a substrate with a short pulse of particles. The particles can be electrons, protons, alpha particles, other atomic or molecular ions or neutral atoms and molecules. The

5 substrate can be composed of a semiconductor material, for example. The particles can include dopant atoms such as p-type dopant atoms such as boron (B), aluminum (Al), gallium (Ga), or indium (In), and n-type dopant atomic species including arsenic (As), phosphorus (P), or antimony (Sb). The particles can also include silicon (Si) or germanium (Ge) atoms or ionized gas atoms including those of hydrogen (He),
10 oxygen (O), nitrogen (N), neon (Ne), argon (Ar), or krypton (Kr). The particles can be used to anneal dopant atoms previously implanted into the substrate.

Alternatively, the particle species can be chosen to include the desired implant dopant, the energy of the particle may be chosen to achieve the desired implant depth, and the energy, dose and pulse duration may be chosen to anneal the
15 implanted region during the pulse. This embodiment of the method performs implantation and activation in a single step. If no change in the electrical state of the substrate is required, the particles can include silicon (Si), and germanium (Ge) atoms.

	1970	1971	1972	1973	1974	1975	1976	1977	1978	1979	1980	1981	1982	1983	1984	1985	1986	1987	1988	1989	1990	1991	1992	1993	1994	1995	1996	1997	1998	1999	2000	2001	2002	2003	2004	2005	2006	2007	2008	2009	2010	2011	2012	2013	2014	2015	2016	2017	2018	2019	2020	2021	2022	2023	2024	2025	2026	2027	2028	2029	2030	2031	2032	2033	2034	2035	2036	2037	2038	2039	2040	2041	2042	2043	2044	2045	2046	2047	2048	2049	2050	2051	2052	2053	2054	2055	2056	2057	2058	2059	2060	2061	2062	2063	2064	2065	2066	2067	2068	2069	2070	2071	2072	2073	2074	2075	2076	2077	2078	2079	2080	2081	2082	2083	2084	2085	2086	2087	2088	2089	2090	2091	2092	2093	2094	2095	2096	2097	2098	2099	2100	2101	2102	2103	2104	2105	2106	2107	2108	2109	2110	2111	2112	2113	2114	2115	2116	2117	2118	2119	2120	2121	2122	2123	2124	2125	2126	2127	2128	2129	2130	2131	2132	2133	2134	2135	2136	2137	2138	2139	2140	2141	2142	2143	2144	2145	2146	2147	2148	2149	2150	2151	2152	2153	2154	2155	2156	2157	2158	2159	2160	2161	2162	2163	2164	2165	2166	2167	2168	2169	2170	2171	2172	2173	2174	2175	2176	2177	2178	2179	2180	2181	2182	2183	2184	2185	2186	2187	2188	2189	2190	2191	2192	2193	2194	2195	2196	2197	2198	2199	2200	2201	2202	2203	2204	2205	2206	2207	2208	2209	2210	2211	2212	2213	2214	2215	2216	2217	2218	2219	2220	2221	2222	2223	2224	2225	2226	2227	2228	2229	2230	2231	2232	2233	2234	2235	2236	2237	2238	2239	2240	2241	2242	2243	2244	2245	2246	2247	2248	2249	2250	2251	2252	2253	2254	2255	2256	2257	2258	2259	2260	2261	2262	2263	2264	2265	2266	2267	2268	2269	2270	2271	2272	2273	2274	2275	2276	2277	2278	2279	2280	2281	2282	2283	2284	2285	2286	2287	2288	2289	2290	2291	2292	2293	2294	2295	2296	2297	2298	2299	2300	2301	2302	2303	2304	2305	2306	2307	2308	2309	2310	2311	2312	2313	2314	2315	2316	2317	2318	2319	2320	2321	2322	2323	2324	2325	2326	2327	2328	2329	2330	2331	2332	2333	2334	2335	2336	2337	2338	2339	2340	2341	2342	2343	2344	2345	2346	2347	2348	2349	2350	2351	2352	2353	2354	2355	2356	2357	2358	2359	2360	2361	2362	2363	2364	2365	2366	2367	2368	2369	2370	2371	2372	2373	2374	2375	2376	2377	2378	2379	2380	2381	2382	2383	2384	2385	2386	2387	2388	2389	2390	2391	2392	2393	2394	2395	2396	2397	2398	2399	2400	2401	2402	2403	2404	2405	2406	2407	2408	2409	2410	2411	2412	2413	2414	2415	2416	2417	2418	2419	2420	2421	2422	2
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Fig. 1A

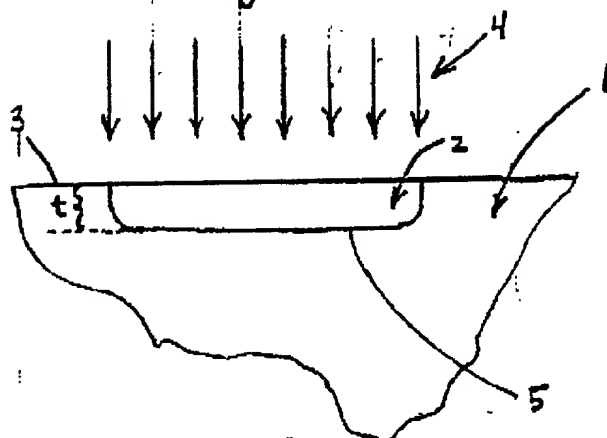


Fig. 1B

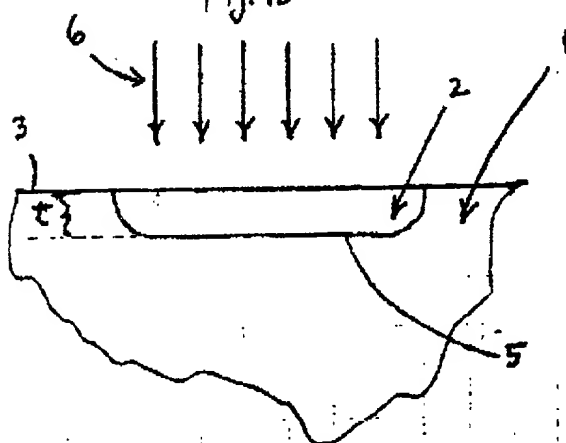


Fig. 1c

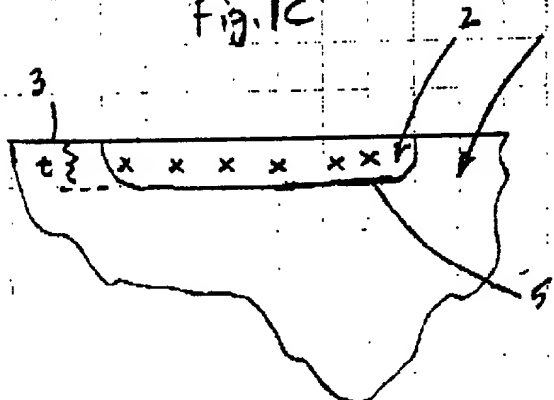


Fig. 2A

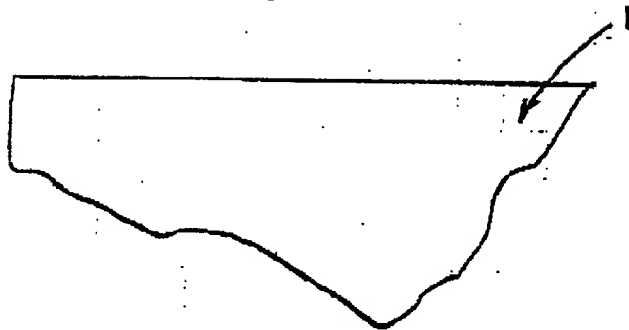


Fig. 2B

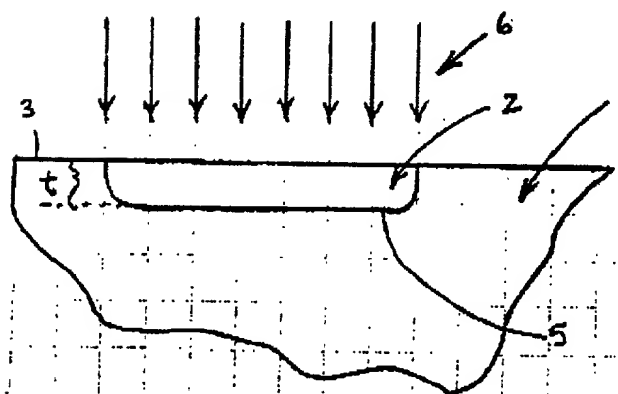


Fig. 2C

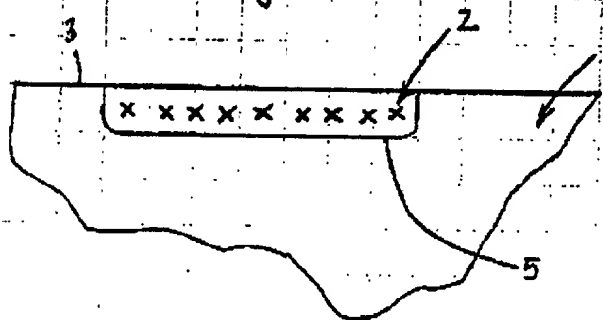
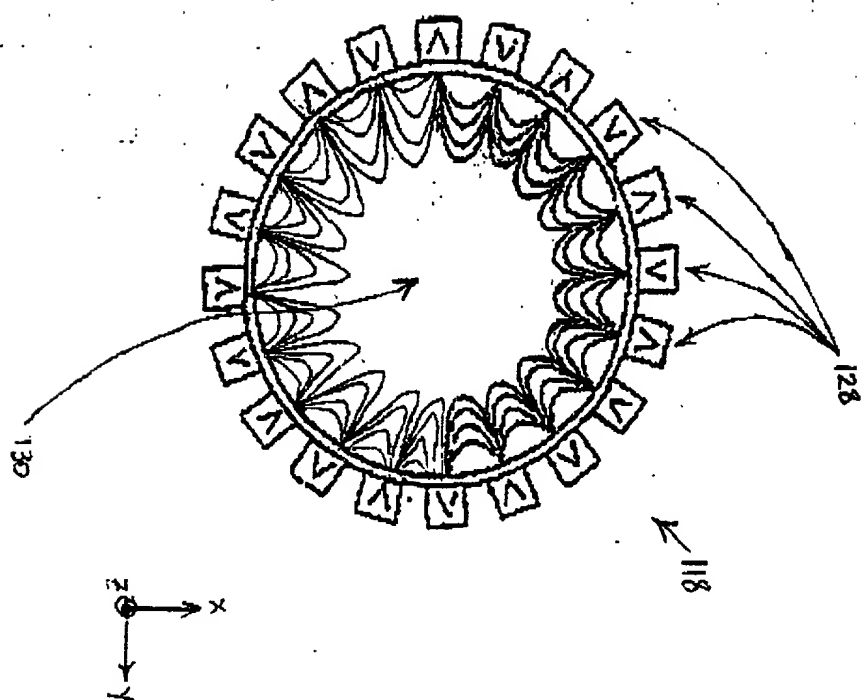


Fig. 4



09536942 00000000

PETERS, VERNY, JONES & BIKŠA, LLP

Attorney's Docket No. 3521.125 (ALJ)

COMBINED DECLARATION AND POWER OF ATTORNEY

*UTILITY, DESIGN, NATIONAL STAGE OF PCT, SUPPLEMENTAL, DIVISIONAL,
CONTINUATION OR CIP APPLICATION*

As a below named inventor, I hereby declare that:

TYPE OF DECLARATION

This declaration is of the following type:

- ☒ utility.
☐ design.
☐ supplemental.

☐ national stage of PCT.

- ☐ divisional.
☐ continuation.
☐ continuation-in-part (CIP).

INVENTORSHIP IDENTIFICATION

My residence, post office address and citizenship are as stated below next to my name, I believe I am the original, first and sole inventor (if only one name is listed below) or an original, first and joint inventor (if plural names are listed below) of the subject matter which is claimed and for which a patent is sought on the invention entitled:

TITLE OF INVENTION

METHODS FOR ANNEALING A SUBSTRATE AND ARTICLE PRODUCED BY SUCH METHODS

SPECIFICATION IDENTIFICATION

the specification of which:

(complete (a), (b) or (c))

- (a) ☒ Is attached hereto.

NOTICE OF JULY 13, 1995 (1177 O.G. 60).

- (b) ☐ was filed on _____, as ☐ Serial No. 0 / _____ or ☐ _____ and was amended on _____ (if applicable).
- (c) ☐ was described and claimed in PCT International Application No. _____, filed on _____ and as amended under PCT Article 19 on _____ (if any).

ACKNOWLEDGMENT OF REVIEW OF PAPERS AND DUTY OF CANDOR

I hereby state that I have reviewed and understand the contents of the above-identified specification, including the claims, as amended by any amendment referred to above.

I acknowledge the duty to disclose information, which is material to patentability as defined in 37, Code of Federal Regulations, §1.56,

(also check the following items, if desired)

- ☐ and which is material to the examination of this application, namely, information where there is a substantial likelihood that a reasonable Examiner would consider it important in deciding whether to allow the application to issue as a patent, and
- ☐ in compliance with this duty, there is attached an information disclosure statement, in accordance with 37 CFR 1.98.

PRIORITY CLAIM (35 U.S.C. § 119(a)-(d))

I hereby claim foreign priority benefits under Title 35, United States Code, § 119(a)-(d) of any foreign application(s) for patent or inventor's certificate or of any PCT international application(s) designating at least one country other than the United States of America listed below and have also identified below any foreign application(s) for patent or inventor's certificate or any PCT international application(s) designating at least one country other than the United States of America filed by me on the same subject matter having a filing date before that of the application(s) of which priority is claimed.

(complete (d) or (e))

- (d) ☒ no such applications have been filed.
- (e) ☐ such applications have been filed as follows

PRIOR FOREIGN/PCT APPLICATION(S), FILED WITHIN 12 MONTHS (6 MONTHS FOR DESIGN) PRIOR TO THIS APPLICATION AND ANY PRIORITY CLAIMS UNDER 35 U.S.C. § 119(a)-(d)

Country (or indicate if PCT)	Application Number	Date of Filing (day, month, year)	Priority Claimed Under 37 USC 119
			<input type="checkbox"/> YES NO <input type="checkbox"/>
			<input type="checkbox"/> YES NO <input type="checkbox"/>
			<input type="checkbox"/> YES NO <input type="checkbox"/>

CLAIM FOR BENEFIT OF PRIOR U.S. PROVISIONAL APPLICATION(S) (34 U.S.C. § 119(e))

I hereby claim the benefit under Title 35, United States Code, § 119(e) of any United States provisional application(s) listed below:

PROVISIONAL APPLICATION NUMBER

FILING DATE

_____/_____
_____/_____

**CLAIM FOR BENEFIT OF PRIOR U.S. PROVISIONAL APPLICATION(S)
UNDER 35 U.S.C. 120**

- ☐ The claim for the benefit of any such applications are set forth in the attached ADDED PAGES TO COMBINED DECLARATION AND POWER OF ATTORNEY FOR DIVISIONAL, CONTINUATION OR CONTINUATION-IN-PART (CIP) APPLICATION.

**ALL FOREIGN APPLICATION(S), IF ANY, FILED MORE THAN 12 MONTHS
(6 MONTHS FOR DESIGN) PRIOR TO THIS U.S. APPLICATION**

- ☐ Attached, as part of this declaration and power of attorney, is the authorization of the above-named attorney(s) to accept and follow instructions from my representative(s).

CONTINUATION-IN-PART

(complete this part only if this is a continuation-in-part application)

I hereby claim the benefit under Title 35, United States Code, § 120 of any United States application(s) listed below and, insofar as the subject matter of each of the claims of this application is not disclosed in the prior United States application in the manner provided by the first paragraph of Title 35, United States Code, § 112, I acknowledge the duty to disclose material information as defined in Title 37, Code of Federal Regulations, § 1.56(a) which occurred between the filing date of the prior application and the national or PCT international filing date of this application.

(Application Serial No.)

(Filing Date)

(Status) (patented, pending, abandoned)

POWER OF ATTORNEY

As a named inventor, I hereby appoint ALLSTON L. JONES, Reg. No. 27,906, HOWARD M. PETERS, Reg. No. 29,202, HANA VERNY, Reg. No. 30,518, JANIS BIKŠA, Reg. No. 33,648, and JON M. JURGOVAN, Reg. No. 34,633 all of the address listed below, my principal attorney and agents, with full power of substitution and revocation, to appoint other principal and associate attorneys, to prosecute this application, and to transact all business in the Patent and Trademark Office connected therewith.

SEND CORRESPONDENCE TO:

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Telephone No.: (650) 324-1677

DECLARATION

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

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CHECK PROPER BOX(ES) FOR ANY ADDED PAGE(S) FORMING A PART OF THIS DECLARATION

- ☐ Signature for fourth and subsequent joint inventors. Number of pages added ____.
- ☐ Signature by administrator, executor(trix) or legal representative for deceased or incapacitated inventor. Number of pages added ____.
- ☐ Signature for inventor who refuses to sign or cannot be reached by person authorized under 37 C.F.R. 1.47. Number of pages added ____.